

Yoon Jang Chung

List of Publications by Year in descending order

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docs citations

39

times ranked

997

citing authors

#	ARTICLE	IF	CITATIONS
1	Correlated States of 2D Electrons near the Landau Level Filling $\frac{1}{2}$. Physical Review Letters, 2022, 128, 026802.	7.8	8
2	Record-quality GaAs two-dimensional hole systems. Physical Review Materials, 2022, 6, .	2.4	12
3	Ultra-high-quality two-dimensional electron systems. Nature Materials, 2021, 20, 632-637.	27.5	76
4	Heterostructure design to achieve high quality, high density GaAs 2D electron system with g-factor tending to zero. Applied Physics Letters, 2020, 117, 022102.	3.3	0
5	Observation of spontaneous ferromagnetism in a two-dimensional electron system. Proceedings of the National Academy of Sciences of the United States of America, 2020, 117, 32244-32250.	7.1	28
6	Working principles of doping-well structures for high-mobility two-dimensional electron systems. Physical Review Materials, 2020, 4, .	2.4	18
7	Spatial Mapping of Local Density Variations in Two-dimensional Electron Systems Using Scanning Photoluminescence. Nano Letters, 2019, 19, 1908-1913.	9.1	7
8	Surface segregation and the Al problem in GaAs quantum wells. Physical Review Materials, 2018, 2, . Multivalley two-dimensional electron system in an AlAs quantum well with mobility exceeding $\frac{1}{2}$ cm2/V\cdot s. Physical Review Letters, 2018, 120, 046802.	2.4	14
9	Design rules for modulation-doped AlAs quantum wells. Physical Review Materials, 2017, 1, .	2.4	16
10	Effects of substrate conductivity on cell morphogenesis and proliferation using tailored, atomic layer deposition-grown ZnO thin films. Scientific Reports, 2015, 5, 9974.	3.3	26
11	Nanoâ€“glass frit for inkjet printed front side metallization of silicon solar cells prepared by solâ€“gel process. Physica Status Solidi - Rapid Research Letters, 2015, 9, 293-296.	2.4	4
12	Indium tin oxide/InGaZnO bilayer stacks for enhanced mobility and optical stability in amorphous oxide thin film transistors. Applied Physics Letters, 2014, 105, .	3.3	24
13	A Simple Method for Cleaning Graphene Surfaces with an Electrostatic Force. Advanced Materials, 2014, 26, 637-644.	21.0	25
14	Growth of p-Type Tin(II) Monoxide Thin Films by Atomic Layer Deposition from Bis(1-dimethylamino-2-methyl-2-propoxy)tin and H₂O. Chemistry of Materials, 2014, 26, 6088-6091.	6.7	76
15	A study on the influence of local doping in atomic layer deposited Al:ZnO thin film transistors. Journal of Materials Chemistry C, 2014, 2, 9274-9282.	5.5	21
16	Fabrication of free-standing Al ₂ O ₃ nanosheets for high mobility flexible graphene field effect transistors. Journal of Materials Chemistry C, 2014, 2, 4759.	5.5	4
17	Synthesis of nitrogen doped graphite oxide and its electrochemical properties. Current Applied Physics, 2014, 14, 82-86.	2.4	27

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19	Trimethylsilylcyclopentadienyl tris(dimethylamino)zirconium as a single-source metal precursor for the atomic layer deposition of ZrxSi1-xO4. <i>Thin Solid Films</i> , 2014, 564, 140-145.	1.8	2
20	Drawing Circuits with Carbon Nanotubes: Scratch-Induced Graphoepitaxial Growth of Carbon Nanotubes on Amorphous Silicon Oxide Substrates. <i>Scientific Reports</i> , 2014, 4, 5289.	3.3	11
21	Study on the defects in metalâ€“organic chemical vapor deposited zinc tin oxide thin films using negative bias illumination stability analysis. <i>Journal of Materials Chemistry C</i> , 2013, 1, 6695.	5.5	18
22	The Electrical Properties of Asymmetric Schottky Contact Thin-Film Transistors with Amorphous-\$hbox{In}_2hbox{Ga}_2hbox{ZnO}_7\$. <i>IEEE Transactions on Electron Devices</i> , 2013, 60, 1128-1135.	3.0	18
23	The charge trapping characteristics of Si3N4 and Al2O3 layers on amorphous-indium-gallium-zinc oxide thin films for memory application. <i>Applied Physics Letters</i> , 2012, 100, 183503.	3.3	20
24	Optical modeling and experimental verification of light induced phenomena in In-Ga-Zn-O thin film transistors with varying gate insulator thickness. <i>Journal of Applied Physics</i> , 2012, 111, 024511.	2.5	8
25	Vertically integrated submicron amorphous-In2Ga2ZnO7 thin film transistor using a low temperature process. <i>Applied Physics Letters</i> , 2012, 100, 203510.	3.3	34
26	Properties of Atomic Layer Deposited HfO ₂ Films on Ge Substrates Depending on Process Temperatures. <i>Journal of the Electrochemical Society</i> , 2012, 159, G33-G39.	2.9	16
27	The Impact of Carbon Concentration on the Crystalline Phase and Dielectric Constant of Atomic Layer Deposited HfO ₂ Films on Ge Substrate. <i>ECS Journal of Solid State Science and Technology</i> , 2012, 1, N33-N37.	1.8	25
28	Reduction of Charge Trapping in \$hbox{HfO}_2\$ Film on Ge Substrates by Atomic Layer Deposition of Various Passivating Interfacial Layers. <i>IEEE Transactions on Electron Devices</i> , 2012, 59, 2350-2356.	3.0	12
29	Performance Variation According to Device Structure and the Source/Drain Metal Electrode of a-IGZO TFTs. <i>IEEE Transactions on Electron Devices</i> , 2012, 59, 3357-3363.	3.0	34
30	Resistive Switching in \$hbox{TiO}_2\$ Thin Films Using the Semiconducting In-Ga-Zn-O Electrode. <i>IEEE Electron Device Letters</i> , 2012, 33, 582-584.	3.9	10
31	Correlation of the change in transfer characteristics with the interfacial trap densities of amorphous Inâ€“Gaâ€“Znâ€“O thin film transistors under light illumination. <i>Applied Physics Letters</i> , 2011, 98, .	3.3	59
32	Improvement in the negative bias illumination temperature stress instability of Inâ€“Gaâ€“Znâ€“O thin film transistors using an Al ₂ O ₃ buffer layer. <i>Physica Status Solidi - Rapid Research Letters</i> , 2011, 5, 178-180.	2.4	15
33	The effects of device geometry on the negative bias temperature instability of Hf-In-Zn-O thin film transistors under light illumination. <i>Applied Physics Letters</i> , 2011, 98, .	3.3	16
34	Direct Observation of Hole Current in Amorphous Oxide Semiconductors under Illumination. <i>Electrochemical and Solid-State Letters</i> , 2011, 14, G35.	2.2	12
35	Study on the Existence of Abnormal Hysteresis in Hf-In-Zn-O Thin Film Transistors under Illumination. <i>Electrochemical and Solid-State Letters</i> , 2011, 14, H300.	2.2	15
36	Amorphous Oxide Semiconductor Memory Using High-k Charge Trap Layer. <i>ECS Transactions</i> , 2010, 33, 375-380.	0.5	0

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37	The Effect of Light Illumination on Transfer Curve and Stability of Amorphous Hf-In-ZnO Thin Film Transistors. ECS Transactions, 2010, 33, 319-324.	0.5	0
38	The Effect of Illumination on the Negative Bias Temperature Instability in Zinc Tin Oxide Thin Film Transistors. ECS Transactions, 2010, 33, 325-330.	0.5	0
39	Spectroscopic Investigation on the Origin of Photoinduced Carrier Generation in Semiconducting InGaO and InGaZnO Films. Journal of Physical Chemistry C, 2010, 114, 11962-11964.	3.1	14